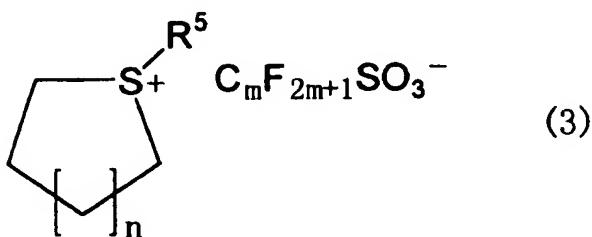


ABSTRACT OF THE DISCLOSURE

A radiation-sensitive resin composition comprising: (A) an acid-dissociable group-containing resin, insoluble or  
5 scarcely soluble in alkali but becoming soluble in alkali when the acid-dissociable group dissociates, and containing recurring units with specific structures and (B) a photoacid generator of the formula (3),



10 wherein R<sup>5</sup> represents a monovalent aromatic hydrocarbon group, m is 1-8, and n is 0-5. The resin composition is suitable as a chemically-amplified resist responsive to deep ultraviolet rays such as a KrF excimer laser and ArF excimer laser, exhibits high transparency, excellent resolution, dry etching  
15 resistance, and sensitivity, produces good pattern shapes, and well adheres to substrates.